

|   | Hits | Search Text   | DBs  |
|---|------|---|--|
| 1 | 10   | 430/394.ccls. and ((first near4 (mask or reticle or phase\$3shift\$4mask)) same (second near5 (mask or reticle or phase\$3shift\$4mask)) same (photoresist or resist or photosensitive) same (substrate or wafer or device) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (first same mask same second same phase same (invers\$3 or revers\$3))  | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB |
| 2 | 40   | ((first near4 (mask or reticle or phase\$3shift\$4mask)) same (second near5 (mask or reticle or phase\$3shift\$4mask)) same (photoresist or resist or photosensitive) same (substrate or wafer or device) same (expos\$4 or irradiat\$4 or illuminat\$4) same first same (second or double or plural\$3)) and (first same mask same second same phase same (invers\$3 or revers\$3))            | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB |
| 3 | 0    | ((first near4 (mask or reticle or phase\$3shift\$4mask)) same (second near5 (mask or reticle or phase\$3shift\$4mask)) same (photoresist or resist or photosensitive) same (substrate or wafer or device) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (first same mask same second same phase same (invers\$3 or revers\$3)) and (projection same (light\$3 or optic\$3) same bracelet) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB |
| 4 | 0    | ((first near4 (mask or reticle or phase\$3shift\$4mask)) same (second near5 (mask or reticle or phase\$3shift\$4mask)) same (photoresist or resist or photosensitive) same (substrate or wafer or device) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (projection same (light\$3 or optic\$3) same  | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB |

|  |  |           |  |
|--|--|-----------|--|
|  |  | bracelet) |  |
|--|--|-----------|--|

|   | Hits | Search Text   | DBs  |
|---|------|---|--|
| 5 | 2    | ((first near4 (mask or reticle or phase\$3shift\$4mask)) same (second near5 (mask or reticle or phase\$3shift\$4mask)) same (photoresist or resist or photosensitive) same (substrate or wafer or device) same (expos\$4 or irradiat\$4 or illuminat\$4)) and ((projection or light\$3 or optic\$3 or expo\$4 or illuminat\$4) same bracelet) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB |
| 6 | 2    | ((projection or light\$3 or optic\$3 or expo\$4 or illuminat\$4) same bracelet) and ((first near4 (mask or reticle or phase\$3shift\$4mask)) same (second near5 (mask or reticle or phase\$3shift\$4mask)) same (photoresist or resist or photosensitive) same (substrate or wafer or device))  | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB |
| 7 | 9    | ((projection or light\$3 or optic\$3 or expo\$4 or illuminat\$4) same bracelet) and ((mask or reticle or phase\$3shift\$4mask) same (photoresist or resist or photosensitive) same (substrate or wafer or device))  | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB |
| 8 | 17   | ((projection or light\$3 or optic\$3 or expo\$4 or illuminat\$4) same bracelet) and ((phase\$4shift near5 mask) or mask or reticle) and ((substrate or wafer or device) same (resist or photoresist))   | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB |

|    | Hits | Search Text  | DBs  |
|----|------|--|--|
| 9  | 24   | ((projection or light\$3 or optic\$3 or expo\$4 or illuminat\$4 or lens or transmitt\$4) same bracelet) and ((phase\$4shift near5 mask) or mask or reticle) and ((substrate or wafer or device) same (resist or photoresist))  | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB |
| 10 | 22   | 430/5.ccls. and ((first near4 (mask or reticle or phase\$3shift\$4mask)) same (second near5 (mask or reticle or phase\$3shift\$4mask)) same (photoresist or resist or photosensitive) same (substrate or wafer or device) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (first same mask same second same phase same (invers\$3 or revers\$3) same shift\$4) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB |